Fred Taber IBM Corporation



Topics:

- **▼Introduction & Background**
- **▼**Considerations & Experiences
- **▼**Q & A

Introduction & Background

- **VVertical Probe Market Growth**
 - -Potentially 40% of the Probe Market Revenue by 2001
 - Technical Drivers

Performance --> Data Rates, Power Distribution, etc.

I/O Requirements --> 2500 and Growing

Packaging --> Multi-Dut (e.g. TCM)

Perimeter Pad Applications

-Business Drivers

• e.g. Cost/Performance, Customer Requirements, etc.....



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Introduction & Background (cont.)

VArea Array Probing History/Experience

-Over 30 Years in IBM

A Variety of Vertical Technologies (Ref. 1) Until......

-COBRA

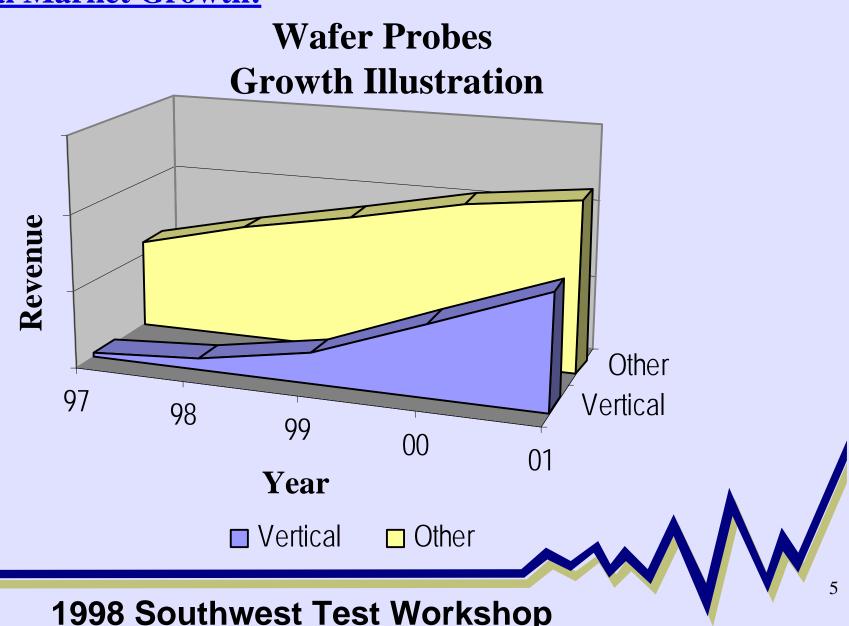
Patented in 1977!! (Ref. 2) Key Enabler Even Today Typical Pitch: .005" on .009"/.010"

- "Vertical" Space Transformer (Fanout)

Wired Ceramic

-Test System & Prober 'Tailoring'

Vertical Market Growth:



Considerations & Experiences:

▼Test System/Methodology/Product

Detecting Power/Ground Shorts

"Soft Power" Protection

AC Performance: Product & Test System Design

Power Distribution Network Power/Ground I/O to Signal I/O Ratio and Placement

- Product

Evaporated or Plated C4's

Low Volume Solder / Height Variations

Run out (Evaporated C4's)

Retest Budget

High Temperature Test --> Greater C4 Pad Deformation

Reflow (If/When and Limits)

Considerations & Experiences (cont.):

VTest Head

Planarity / Co-Planarity

Set-ups May Differ By Probe Technology

Deformation/Movement

Higher Probe Forces
Probe Technology Dependent

Wafer Prober

Alignment

Look-up Optics Larger Probing Window/Target

Chuck

High Z Force
Tilt Issues at Edge

Considerations & Experiences (cont.):

Wafer Probe

Mechanical Specifications

I/O & DUT Capacity

Pitch Boundaries

PbSn Pick-up / Removal

- Electrical Performance

Bandwidth

Near-in Decoupling

Sub-System Contributions (Space Transformer, DUT Board, etc.)

Bulk & Contact Resistance

Current Carrying Capacity

C4 Deformation Effects

Probe Technology Dependent

Retest Capability

Voids Occurring After Reflow --> Reliability Issue

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Considerations & Experiences (cont.):

Wafer Probe

Manufacturing Considerations

Robustness
Set-up/Replacement/Repairability
COO

Source of Supply

Limited Offerings /Suppliers Today Second-Sourcing

- Planarity / Compliance / Cleaning Effects

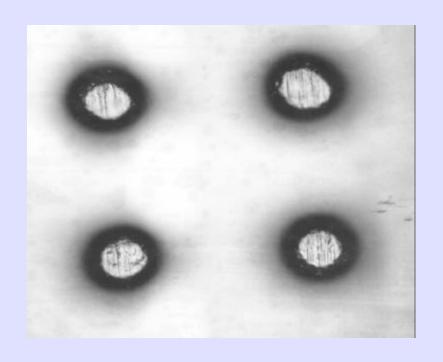
Probe Life

Force / Deflection - Operating Point/Range

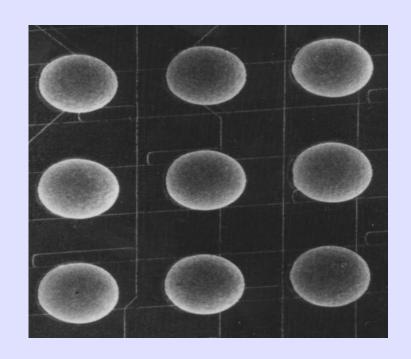
Contact Resistance Vs. Number of Touch Downs

Cleaning Techniques: Abrasive, In-situ?

C4 Deformation / Reflow:



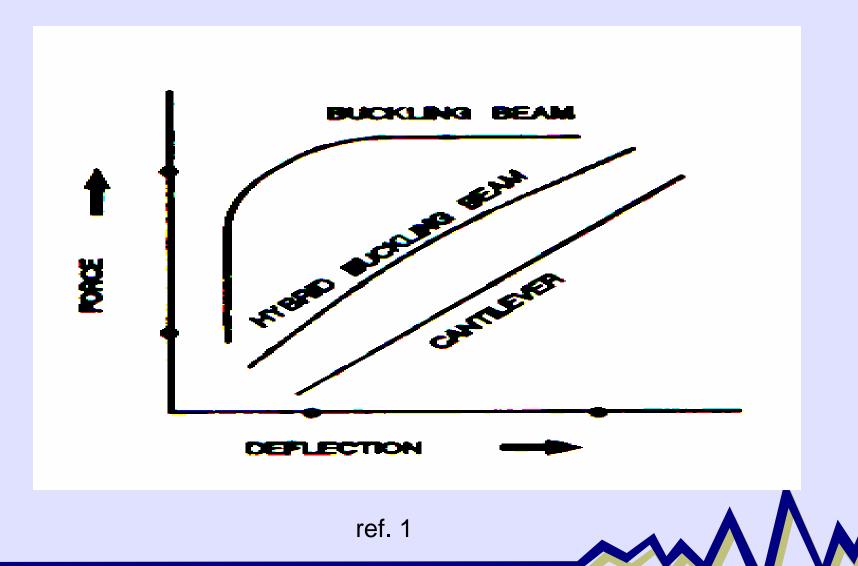
After COBRA Probing (Optical 200x)



After Reflow (SEM)

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Force / Deflection Curves:



Q & A:

- **▼What Are Your Experiences?**
- **V**Any Questions?



References & Acknowledgements:

- **Ref.** 1

"Probing Considerations In C-4 Testing Of IC Wafers" by Dennis J. Genin and Manfred Wurster, IBM Corporation, 1992

- **Ref. 2**

United States Patent #4,027,935; June 7, 1977; "Contact For An Electrical Contactor Assembly"; Herbert Byrnes and Richard Wahl (Assignee: IBM)

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